



## ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18  
Stylesheet Version v18.0

<b>Title of Invention</b>	Inspection System By Charged Particle Beam And Method Of Manufacturing Devices Using The System																
Application Number: 09/891611 Confirmation Number: 8874 First Named Applicant: Mamoru Makasuji Attorney Docket Number: 010817 Art Unit: 2881 Examiner: Jack I Berman Search string: ( 5578821 ).pn.																	
<b>US Patent Documents</b>  Note: Applicant is not required to submit a paper copy of cited US Patent Documents																	
<table border="1"><thead><tr><th>Init</th><th>Cite.No.</th><th>Patent No.</th><th>Date</th><th>Patentee</th><th>Kind</th><th>Class</th><th>Subclass</th></tr></thead><tbody><tr><td><i>OK</i></td><td>1</td><td>5578821</td><td>1996-11-26</td><td>Meisberger et al</td><td></td><td>250</td><td>310</td></tr></tbody></table>		Init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass	<i>OK</i>	1	5578821	1996-11-26	Meisberger et al		250	310
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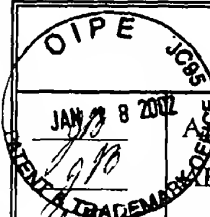
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<b>INFORMATION DISCLOSURE CITATION PTO-1449</b>	Atty. Docket No. 010817	Serial No. 09/891,611
	Applicant: Mamoru NAKASUJI et al.	
	Filing Date: June 27, 2001	Group Art Unit:

**FOREIGN PATENT DOCUMENTS**

	Document No.	Date	Country	Translation (Yes or No)
	52-115161 ✓	09/27/77	JAPAN	ABSTRACT
	52-117567 ✓	10/03/77	JAPAN	ABSTRACT
	57-072326 ✓	05/06/82	JAPAN	ABSTRACT
	57-125871 ✓	08/05/82	JAPAN	ABSTRACT
	60-000741 ✓	01/05/85	JAPAN	ABSTRACT
	62-195838 ✓	08/28/87	JAPAN	ABSTRACT
	03-022339 ✓	01/30/91	JAPAN	ABSTRACT
	03-053439 ✓	03/07/91	JAPAN	ABSTRACT
	03-102814 ✓	04/30/91	JAPAN	ABSTRACT
	03-266350 ✓	11/27/91	JAPAN	ABSTRACT
	03-276548 ✓	12/06/91	JAPAN	ABSTRACT
	04-266350 ✓	09/22/92	JAPAN	ABSTRACT
	05-063261 ✓	03/12/93	JAPAN	ABSTRACT
	05-251316 ✓	09/28/93	JAPAN	ABSTRACT
	07-065766 ✓	03/10/95	JAPAN	ABSTRACT
	08-138611 ✓	05/31/96	JAPAN	ABSTRACT
	09-311112 ✓	12/02/97	JAPAN	ABSTRACT
	10-062503 ✓	03/06/98	JAPAN	ABSTRACT
	10-177952 ✓	06/30/98	JAPAN	ABSTRACT
	11-132975 ✓	05/21/99	JAPAN	ABSTRACT
	2000-090868 ✓	03/31/00	JAPAN	ABSTRACT

Examiner <i>Jack Berman</i>	Date Considered <i>10/22/07</i>
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<b>INFORMATION DISCLOSURE CITATION PTO-1449</b>	Atty. Docket No. 010817	Serial No. 09/891,611
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### U.S. PATENT DOCUMENTS

Examiner Initial	Document No.	Name	Date	Class	Subclass	Filing Date (If appropriate)
<i>GP</i>	AV	6,125,522	Nakasuji	10/03/00		11/12/96
<i>GP</i>	W	6,087,667	Nakasuji et al.	07/11/00		09/30/97
<i>GP</i>	X	5,994,704	Nakasuji	11/30/99		10/03/97
<i>GP</i>	AY	5,981,947	Nakasuji et al.	11/09/99		02/03/98
<i>GP</i>	AZ	5,892,224	Nakasuji	04/06/99		05/09/97
<i>GP</i>	BA	5,770,863	Nakasuji	06/23/98		10/24/96
<i>GP</i>	BB	5,763,893	Nakasuji	06/09/98		12/16/96
<i>GP</i>	BC	5,751,538	Nakasuji	05/12/98		09/26/96
<i>GP</i>	BD	5,747,819	Nakasuji et al.	05/05/98		10/30/96
<i>GP</i>	BE	5,362,968	Miyoshi et al.	11/08/94		09/27/93
<i>GP</i>	BF	5,359,197	Komatsu et al.	10/25/94		07/16/93
<i>GP</i>	BG	4,912,052	Miyoshi et al.	03/27/90		09/23/88

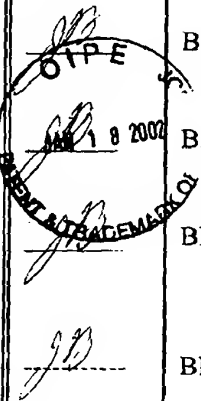
### OTHER DOCUMENTS

<i>GP</i>	BH ✓	<i>Low Voltage and high speed operating electrostatic wafer chuck using sputtered tantalum oxide membrane, Mamoru Nakasuji et al., J. Vac. Sci. Technol. A 12(5), Sep/Oct 1994, American Vacuum Society pp. 2834-2839.</i>				
<i>GP</i>	BI ✓	<i>High -Emittance and Low-Brightness Electron Gun for Reducing-Image Projection System: Computer Simulation, Mamoru Nakasuji et al., Jpn. J. Appl. Phys. Vol. 36 (1997) pp.2404-2408.</i>				
<i>GP</i>	BJ ✓	<i>H. Hayashi, et al., LSI Testing Symposium 1998, Minutes of the meeting, P160 (1998) (partial translation)</i>				
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## OTHER DOCUMENTS

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	BK ✓	Multi-Beam Concepts for Nanometer Devices, B. Lischke et al., Japanese Journal of Applied Physics, Vol. 28, No.10, October 1989, pp. 2058-2064.
	BL ✓	An electron-beam inspecting system for x-ray mask production, P. Sandland et al., J. Vac. Sci. Technol. B9 (6), Nov/Dec. 1991, American Vacuum Society, pp.3005-3009.
	BM ✓	Requirements and performance of an electron-beam column designed for x-ray mask inspection, W.D. Meisburger et al., J. Vac. Sci. Technol. B9 (6), Nov/Dec 1991, American Vacuum Society, pp.3010-3014.
	BN ✓	Table 5-1 Work Function in Metals page 116.

Examiner <i>Jack Berman</i>	Date Considered <i>10/22/03</i>
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